



Docket No.: SON-2628
(PATENT)

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:
Shinji Omori

Application No.: 10/509,230

Confirmation No.: 1800

Filed: September 24, 2004

Art Unit: 2812

For: MASK PATTERN CORRECTION METHOD,
PRODUCTION METHOD OF
SEMICONDUCTOR DEVICE, MASK
PRODUCTION METHOD AND MASK

Examiner: Not Yet Assigned

FIRST PRELIMINARY AMENDMENT

MS Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Dear Sir:

INTRODUCTORY COMMENTS

Prior to examination on the merits, please amend the above-identified U.S. patent application as follows: